

PATTERN FOR IMPROVED VISUAL INSPECTION  
OF SEMICONDUCTOR DEVICES

ABSTRACT OF THE DISCLOSURE

5           A semiconductor structure is disclosed that enhances quality control inspection of  
device. The structure includes a substrate having at least one planar face, a first metal layer  
on the planar face, and covering some, but not all of the planar face in a first predetermined  
geometric pattern, and a second metal layer on the planar face, and covering some, but not all  
of the planar face in a second geometric pattern that is different from the first geometric  
10       pattern. A quality control method for manufacturing a semiconductor device is also  
disclosed. The method includes the steps of placing a first metal layer on a semiconductor  
face of a device in a first predetermined geometric pattern, placing a second metal layer on  
the same face of the device as the first layer and in a second predetermined geometric pattern  
that is different from the first geometric pattern, and then inspecting the device to identify the  
15       presence or absence of one or both of the patterns on the face.

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